

=> d his

• (FILE 'HOME' ENTERED AT 17:59:41 ON 20 MAY 2003)

FILE 'REGISTRY' ENTERED AT 17:59:56 ON 20 MAY 2003

L1 SCREEN 964 AND 970 AND 1015 AND 1051  
L2 STRUCTURE uploaded  
L3 QUE L2 AND L1  
L4 0 S L3 SSS SAM

FILE 'CAPLUS, HCPLUS, USPATFULL, USPAT2' ENTERED AT 18:00:24 ON 20 MAY 2003

L5 0 S L4

FILE 'REGISTRY' ENTERED AT 18:00:51 ON 20 MAY 2003

L6 SCREEN 964 AND 970 AND 1015 AND 1051 AND 2067  
L7 STRUCTURE uploaded  
L8 QUE L7 AND L6  
L9 0 S L8 SSS SAM

FILE 'CAPLUS, HCPLUS, USPATFULL, USPAT2' ENTERED AT 18:01:15 ON 20 MAY 2003

L10 0 S L9

FILE 'REGISTRY' ENTERED AT 18:01:25 ON 20 MAY 2003

L11 0 S 1-HYDROXY-3-1-ACRYLOYLOXY-12-DIMETHYLPROPYLADAMANTINE  
L12 0 S 1-HYDROXY-3-1-ACRYLOYLOXY-12-DIMETHYLPROPYL ADAMANTINE  
L13 0 S 1-HYDROXY-3-1-ACRYLOYLOXY-12-DIMETHYLPROPYL ADAMANTANE  
L14 0 S 1-HYDROXY-3-1-ACRYLOYLOXY-12-DIMETHYLPROPYLADAMANTANE

FILE 'HOME' ENTERED AT 18:03:18 ON 20 MAY 2003

FILE 'REGISTRY' ENTERED AT 18:07:37 ON 20 MAY 2003

L15 SCREEN 970 AND 2067  
L16 STRUCTURE uploaded  
L17 QUE L16 AND L15  
L18 5 S L17 SSS SAM

SIN-CAS  
Search  
DO NOT Remove

FILE 'CAPLUS, HCPLUS, USPATFULL, USPAT2' ENTERED AT 18:08:32 ON 20 MAY 2003

L19 17 S L18  
L20 8 DUPLICATE REMOVE L19 (9 DUPLICATES REMOVED)

FILE 'HOME' ENTERED AT 18:09:19 ON 20 MAY 2003

FILE 'REGISTRY' ENTERED AT 18:10:06 ON 20 MAY 2003

L21 SCREEN 970 AND 2076 AND 2067  
L22 STRUCTURE uploaded  
L23 QUE L22 AND L21  
L24 0 S L23

FILE 'CAPLUS, HCPLUS, USPATFULL, USPAT2' ENTERED AT 18:10:45 ON 20 MAY 2003

L25 0 S L24

FILE 'HOME' ENTERED AT 18:10:54 ON 20 MAY 2003

FILE 'REGISTRY' ENTERED AT 18:13:10 ON 20 MAY 2003

L26 SCREEN 970 AND 2067  
L27 STRUCTURE uploaded  
L28 QUE L27 AND L26  
L29 0 S L28 SSS SAM

FILE 'CAPLUS, HCAPLUS, USPATFULL, USPAT2' ENTERED AT 18:13:35 ON 20 MAY  
2003

L30

O S L29

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=> ....Testing the current file.... screen  
ENTER SCREEN EXPRESSION OR (END) :end  
  
=> screen 970 AND 2067
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L15 SCREEN CREATED

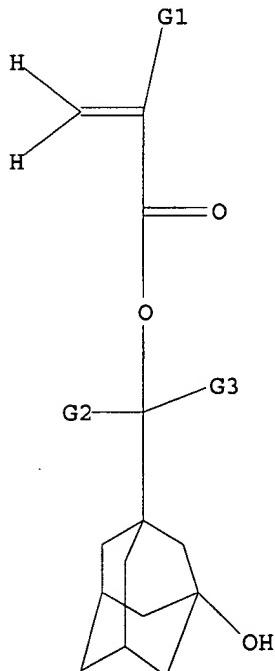
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Uploading C:\Program Files\Stnexp\Queries\09463059.str
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L16 STRUCTURE UPLOADED

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=> que L16 AND L15
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L17 QUE L16 AND L15

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=> d  
L17 HAS NO ANSWERS  
L15 SCR 970 AND 2067  
L16 STR
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G1 Me,H  
G2 H,Ak,Cy  
G3 Cy,Ak

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Structure attributes must be viewed using STN Express query preparation.  
L17 QUE ABB=ON PLU=ON L16 AND L15
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=> s l17 sss sam  
SAMPLE SEARCH INITIATED 18:08:17 FILE 'REGISTRY'  
SAMPLE SCREEN SEARCH COMPLETED - 7 TO ITERATE
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100.0% PROCESSED 7 ITERATIONS

5 ANSWERS

SEARCH TIME: 00.00.01

FULL FILE PROJECTIONS: ONLINE \*\*COMPLETE\*\*  
BATCH \*\*COMPLETE\*\*  
PROJECTED ITERATIONS: 7 TO 298  
PROJECTED ANSWERS: 5 TO 234

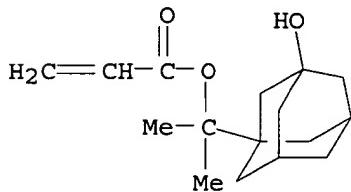
L18 5 SEA SSS SAM L16 AND L15

=> d

L18 ANSWER 1 OF 5 REGISTRY COPYRIGHT 2003 ACS  
RN 450410-08-9 REGISTRY  
CN 2-Propenoic acid, 3,5-dihydroxytricyclo[3.3.1.13,7]dec-1-yl ester, polymer  
with 1-(3-hydroxytricyclo[3.3.1.13,7]dec-1-yl)-1-methylethyl 2-propenoate  
(9CI) (CA INDEX NAME)  
MF (C16 H24 O3 . C13 H18 O4)x  
CI PMS  
PCT Polyacrylic  
SR CA  
LC STN Files: CA, CAPLUS, USPATFULL

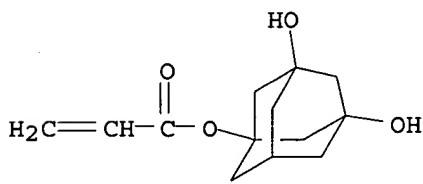
CM 1

CRN 262608-27-5  
CMF C16 H24 O3



CM 2

CRN 216581-85-0  
CMF C13 H18 O4



1 REFERENCES IN FILE CA (1957 TO DATE)  
1 REFERENCES IN FILE CAPLUS (1957 TO DATE)

=> FIL CAPLUS HCAPLUS USPATFULL USPAT2

COST IN U.S. DOLLARS

SINCE FILE  
ENTRY

FULL ESTIMATED COST

TOTAL  
SESSION  
2.48 143.18

FILE 'CAPLUS' ENTERED AT 18:08:32 ON 20 MAY 2003  
USE IS SUBJECT TO THE TERMS OF YOUR STN CUSTOMER AGREEMENT.

PLEASE SEE "HELP USAGETERMS" FOR DETAILS.  
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FILE 'HCAPLUS' ENTERED AT 18:08:32 ON 20 MAY 2003  
USE IS SUBJECT TO THE TERMS OF YOUR STN CUSTOMER AGREEMENT.  
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FILE 'USPATFULL' ENTERED AT 18:08:32 ON 20 MAY 2003  
CA INDEXING COPYRIGHT (C) 2003 AMERICAN CHEMICAL SOCIETY (ACS)

FILE 'USPAT2' ENTERED AT 18:08:32 ON 20 MAY 2003  
CA INDEXING COPYRIGHT (C) 2003 AMERICAN CHEMICAL SOCIETY (ACS)

=> d his

(FILE 'HOME' ENTERED AT 17:59:41 ON 20 MAY 2003)

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L1 SCREEN 964 AND 970 AND 1015 AND 1051  
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L3 QUE L2 AND L1  
L4 O S L3 SSS SAM

FILE 'CAPLUS, HCAPLUS, USPATFULL, USPAT2' ENTERED AT 18:00:24 ON 20 MAY  
2003  
L5 O S L4

FILE 'REGISTRY' ENTERED AT 18:00:51 ON 20 MAY 2003  
L6 SCREEN 964 AND 970 AND 1015 AND 1051 AND 2067  
L7 STRUCTURE uploaded  
L8 QUE L7 AND L6  
L9 O S L8 SSS SAM

FILE 'CAPLUS, HCAPLUS, USPATFULL, USPAT2' ENTERED AT 18:01:15 ON 20 MAY  
2003  
L10 O S L9

FILE 'REGISTRY' ENTERED AT 18:01:25 ON 20 MAY 2003  
L11 O S 1-HYDROXY-3-1-ACRYLOYLOXY-12-DIMETHYLPROPYLADAMANTINE  
L12 O S 1-HYDROXY-3-1-ACRYLOYLOXY-12-DIMETHYLPROPYL ADAMANTINE  
L13 O S 1-HYDROXY-3-1-ACRYLOYLOXY-12-DIMETHYLPROPYL ADAMANTANE  
L14 O S 1-HYDROXY-3-1-ACRYLOYLOXY-12-DIMETHYLPROPYLADAMANTANE

FILE 'HOME' ENTERED AT 18:03:18 ON 20 MAY 2003

FILE 'REGISTRY' ENTERED AT 18:07:37 ON 20 MAY 2003  
L15 SCREEN 970 AND 2067  
L16 STRUCTURE uploaded  
L17 QUE L16 AND L15  
L18 5 S L17 SSS SAM

FILE 'CAPLUS, HCAPLUS, USPATFULL, USPAT2' ENTERED AT 18:08:32 ON 20 MAY  
2003

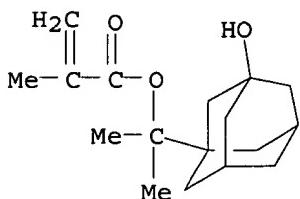
=> s l18  
L19 17 L18

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ENTER L# LIST OR (END):l19  
DUPLICATE PREFERENCE IS 'CAPLUS, HCAPLUS, USPATFULL'  
KEEP DUPLICATES FROM MORE THAN ONE FILE? Y/(N):n  
PROCESSING COMPLETED FOR L19  
L20 8 DUPLICATE REMOVE L19 (9 DUPLICATES REMOVED)

=> d 120 1-8 ibib hitstr

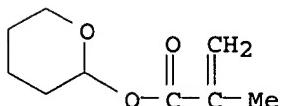
L20 ANSWER 1 OF 8 CAPLUS COPYRIGHT 2003 ACS DUPLICATE 1  
ACCESSION NUMBER: 2002:654986 CAPLUS  
DOCUMENT NUMBER: 137:192769  
TITLE: Polymeric compound and resin composition for photoresist  
INVENTOR(S): Ushirogouchi, Toru; Okino, Takeshi; Asakawa, Koji; Shida, Naomi; Funaki, Yoshinori; Tsutsumi, Kiyoharu; Takaragi, Akira; Inoue, Keizo  
PATENT ASSIGNEE(S): Kabushiki Kaisha Toshiba, Japan; Daicel Chemical Industries, Ltd.  
SOURCE: U.S., 24 pp.  
CODEN: USXXAM  
DOCUMENT TYPE: Patent  
LANGUAGE: English  
FAMILY ACC. NUM. COUNT: 1  
PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
US 6440636	B1	20020827	US 2000-703677	20001102
PRIORITY APPLN. INFO.:			US 2000-703677	20001102
IT 338790-67-3P	450410-08-9P			!! - 2-00
RL: PRP (Properties); SPN (Synthetic preparation); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses) (polymeric compd. and resin compn. for photoresist)				
RN 338790-67-3	CAPLUS			
CN 2-Propenoic acid, 2-methyl-, 1-(3-hydroxytricyclo[3.3.1.13,7]dec-1-yl)-1-methylethyl ester, polymer with tetrahydro-2H-pyran-2-yl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)				
CM 1				
CRN 324761-49-1				
CMF C17 H26 O3				



CM 2

CRN 52858-59-0  
CMF C9 H14 O3

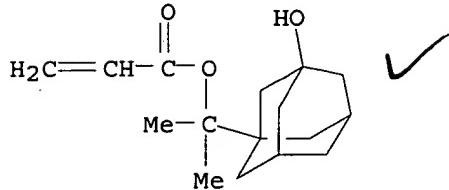


RN 450410-08-9 CAPLUS  
CN 2-Propenoic acid, 3,5-dihydroxytricyclo[3.3.1.13,7]dec-1-yl ester, polymer with 1-(3-hydroxytricyclo[3.3.1.13,7]dec-1-yl)-1-methylethyl 2-propenoate

(9CI) (CA INDEX NAME)

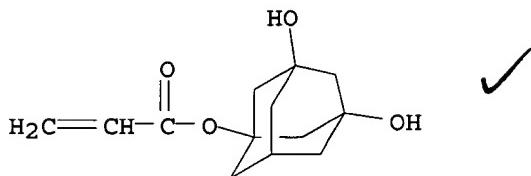
CM 1

CRN 262608-27-5  
CMF C16 H24 O3



CM 2

CRN 216581-85-0  
CMF C13 H18 O4



REFERENCE COUNT: 13 THERE ARE 13 CITED REFERENCES AVAILABLE FOR THIS RECORD. ALL CITATIONS AVAILABLE IN THE RE FORMAT

L20 ANSWER 2 OF 8 CAPLUS COPYRIGHT 2003 ACS DUPLICATE 2  
ACCESSION NUMBER: 2002:292089 CAPLUS  
DOCUMENT NUMBER: 136:316934  
TITLE: Positive-working photoresist composition for fabrication of semiconductor device  
INVENTOR(S): Sato, Kenichiro  
PATENT ASSIGNEE(S): Fuji Photo Film Co., Ltd., Japan  
SOURCE: Jpn. Kokai Tokkyo Koho, 51 pp.  
CODEN: JKXXAF  
DOCUMENT TYPE: Patent  
LANGUAGE: Japanese  
FAMILY ACC. NUM. COUNT: 1  
PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 2002116544	A2	20020419	JP 2000-310761	20001011
PRIORITY APPLN. INFO.:			JP 2000-310761	20001011

OTHER SOURCE(S): MARPAT 136:316934

IT 412015-88-4

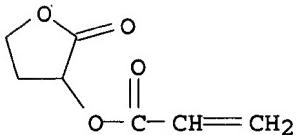
RL: TEM (Technical or engineered material use); USES (Uses)  
(pos.-working photoresist compn. for fabrication of semiconductor device)

RN 412015-88-4 CAPLUS

CN 2-Propenoic acid, 1-(3-hydroxytricyclo[3.3.1.13,7]dec-1-yl)-1-methylethyl ester, polymer with 2,5-furandione, 1,2,3,4,4a,5,8,8a-octahydro-1,4:5,8-dimethanonaphthalene and tetrahydro-2-oxo-3-furanyl 2-propenoate (9CI)  
(CA INDEX NAME)

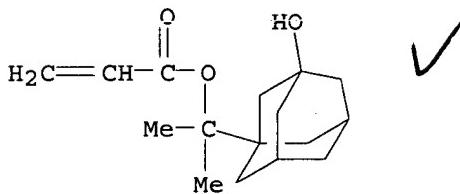
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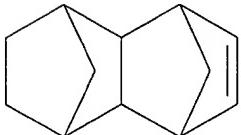
CM 2

CRN 262608-27-5  
CMF C16 H24 O3



CM 3

CRN 21635-90-5  
CMF C12 H16



CM 4

CRN 108-31-6  
CMF C4 H2 O3



L20 ANSWER 3 OF 8 CAPLUS COPYRIGHT 2003 ACS

DUPPLICATE 3

ACCESSION NUMBER: 2001:347119 CAPLUS

DOCUMENT NUMBER: 134:346475

TITLE: Adamantyl-containing polymer for photoresist and polymer composition for photoresist

INVENTOR(S): Gokochi, Toru; Okino, Takeshi; Asakawa, Koji; Shinoda, Naomi; Funaki, Katsunori; Tsutsumi, Kiyoharu; Horai,

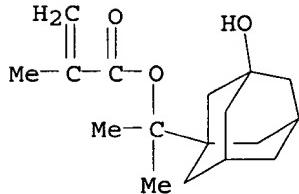
PATENT ASSIGNEE(S): Akira; Inoue, Keizo  
 Toshiba Corp., Japan; Daicel Chemical Industries, Ltd.  
 SOURCE: Jpn. Kokai Tokkyo Koho, 23 pp.  
 CODEN: JKXXAF  
 DOCUMENT TYPE: Patent  
 LANGUAGE: Japanese  
 FAMILY ACC. NUM. COUNT: 1  
 PATENT INFORMATION:

5/15/01

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 2001131232	A2	20010515	JP 1999-312329	19991102
PRIORITY APPLN. INFO.:			JP 1999-312329	19991102
IT 338790-67-3P				11-2-99
RL: IMF (Industrial manufacture); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses) (adamantyl-contg. polymer for etching-resistant photoresist for semiconductor device fabrication)				
RN 338790-67-3 CAPLUS				
CN 2-Propenoic acid, 2-methyl-, 1-(3-hydroxytricyclo[3.3.1.13,7]dec-1-yl)-1-methylethyl ester, polymer with tetrahydro-2H-pyran-2-yl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)				

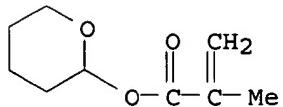
CM 1

CRN 324761-49-1  
CMF C17 H26 O3



CM 2

CRN 52858-59-0  
CMF C9 H14 O3



L20 ANSWER 4 OF 8 CAPLUS COPYRIGHT 2003 ACS DUPLICATE 4  
 ACCESSION NUMBER: 2001:117245 CAPLUS  
 DOCUMENT NUMBER: 134:170832  
 TITLE: Positive-working photoresist composition suitable for exposed with ArF excimer laser  
 INVENTOR(S): Sato, Kenichiro; Shirakawa, Hiroshi; Aogo, Toshiaki  
 PATENT ASSIGNEE(S): Fuji Photo Film Co., Ltd., Japan  
 SOURCE: Jpn. Kokai Tokkyo Koho, 48 pp.  
 CODEN: JKXXAF  
 DOCUMENT TYPE: Patent  
 LANGUAGE: Japanese  
 FAMILY ACC. NUM. COUNT: 1

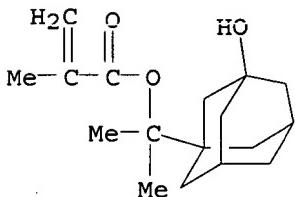
## PATENT INFORMATION:

2/16/01

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 2001042535	A2	20010216	JP 1999-211370	19990726
PRIORITY APPLN. INFO.:			JP 1999-211370	19990726

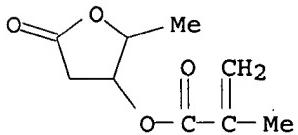
IT 324761-53-7P 324761-58-2P  
 RL: SPN (Synthetic preparation); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)  
 (alicyclic polymer in pos.-working photoresist compn.)  
 RN 324761-53-7 CAPLUS  
 CN 2-Propenoic acid, 2-methyl-, 1-(3-hydroxytricyclo[3.3.1.13,7]dec-1-yl)-1-methylethyl ester, polymer with tetrahydro-2-methyl-5-oxo-3-furanyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

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CRN 324761-49-1  
CMF C17 H26 O3

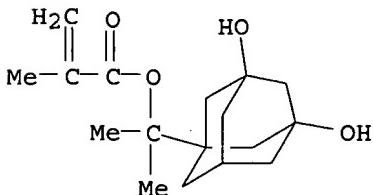
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CM 2

CRN 324761-23-1  
CMF C9 H12 O4

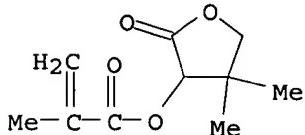
RN 324761-58-2 CAPLUS  
 CN 2-Propenoic acid, 2-methyl-, 1-(3,5-dihydroxytricyclo[3.3.1.13,7]dec-1-yl)-1-methylethyl ester, polymer with tetrahydro-4,4-dimethyl-2-oxo-3-furanyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 324761-57-1  
CMF C17 H26 O4

CM 2

CRN 156938-13-5  
CMF C10 H14 O4



L20 ANSWER 5 OF 8 CAPLUS COPYRIGHT 2003 ACS DUPLICATE 5  
ACCESSION NUMBER: 2001:117244 CAPLUS  
DOCUMENT NUMBER: 134:170858  
TITLE: Positive-working photoresist composition suitable for exposed with ArF excimer laser  
INVENTOR(S): Sato, Kenichiro; Shirakawa, Hiroshi; Aogo, Toshiaki  
PATENT ASSIGNEE(S): Fuji Photo Film Co., Ltd., Japan  
SOURCE: Jpn. Kokai Tokkyo Koho, 48 pp.  
CODEN: JKXXAF  
DOCUMENT TYPE: Patent  
LANGUAGE: Japanese  
FAMILY ACC. NUM. COUNT: 1  
PATENT INFORMATION:

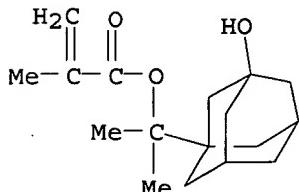
2/16/01

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 2001042534	A2	20010216	JP 1999-211369	19990726
PRIORITY APPLN. INFO.:			JP 1999-211369	19990726

IT 324761-53-7P 324761-58-2P  
RL: SPN (Synthetic preparation); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)  
(alicyclic polymer in pos.-working photoresist compn.)  
RN 324761-53-7 CAPLUS  
CN 2-Propenoic acid, 2-methyl-, 1-(3-hydroxytricyclo[3.3.1.13,7]dec-1-yl)-1-methylethyl ester, polymer with tetrahydro-2-methyl-5-oxo-3-furanyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

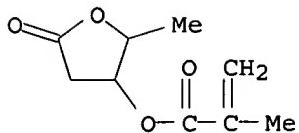
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CM 2

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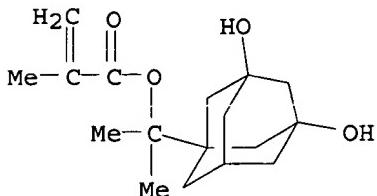
RN 324761-58-2 CAPLUS

CN 2-Propenoic acid, 2-methyl-, 1-(3,5-dihydroxytricyclo[3.3.1.13,7]dec-1-yl)-1-methylethyl ester, polymer with tetrahydro-4,4-dimethyl-2-oxo-3-furanyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 324761-57-1

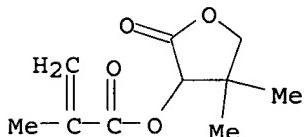
CMF C17 H26 O4



CM 2

CRN 156938-13-5

CMF C10 H14 O4



L20 ANSWER 6 OF 8 CAPLUS COPYRIGHT 2003 ACS

DUPLICATE 6

ACCESSION NUMBER: 2001:117243 CAPLUS

DOCUMENT NUMBER: 134:170831

TITLE: Positive-working photoresist composition suitable for exposed with ArF excimer laser

INVENTOR(S): Sato, Kenichiro; Shirakawa, Hiroshi; Aogo, Toshiaki

PATENT ASSIGNEE(S): Fuji Photo Film Co., Ltd., Japan

SOURCE: Jpn. Kokai Tokkyo Koho, 47 pp.

CODEN: JKXXAF

DOCUMENT TYPE: Patent

LANGUAGE: Japanese

FAMILY ACC. NUM. COUNT: 1

PATENT INFORMATION:

2/16/01

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 2001042533	A2	20010216	JP 1999-211368	19990726
PRIORITY APPLN. INFO.:			JP 1999-211368	19990726

IT 324761-53-7P 324761-58-2P

RL: SPN (Synthetic preparation); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)  
 (alicyclic polymer in pos.-working photoresist compn.)

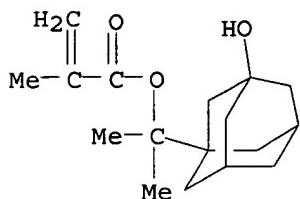
RN 324761-53-7 CAPLUS

CN 2-Propenoic acid, 2-methyl-, 1-(3-hydroxytricyclo[3.3.1.13,7]dec-1-yl)-1-methylethyl ester, polymer with tetrahydro-2-methyl-5-oxo-3-furanyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 324761-49-1

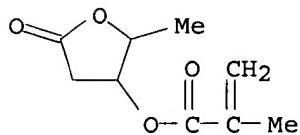
CMF C17 H26 O3



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CRN 324761-23-1

CMF C9 H12 O4



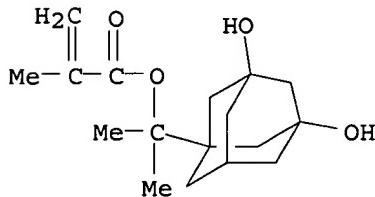
RN 324761-58-2 CAPLUS

CN 2-Propenoic acid, 2-methyl-, 1-(3,5-dihydroxytricyclo[3.3.1.13,7]dec-1-yl)-1-methylethyl ester, polymer with tetrahydro-4,4-dimethyl-2-oxo-3-furanyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 324761-57-1

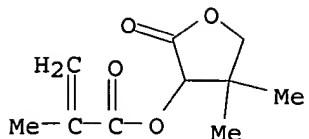
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CM 2

CRN 156938-13-5

CMF C10 H14 O4



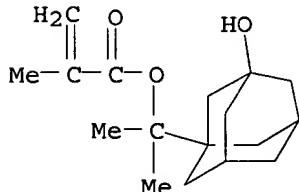
L20 ANSWER 7 OF 8 CAPLUS COPYRIGHT 2003 ACS DUPLICATE 7  
 ACCESSION NUMBER: 2001:117242 CAPLUS  
 DOCUMENT NUMBER: 134:170830  
 TITLE: Positive-working photoresist composition suitable for  
 exposed with ArF excimer laser  
 INVENTOR(S): Sato, Kenichiro; Shirakawa, Hiroshi; Aogo, Toshiaki  
 PATENT ASSIGNEE(S): Fuji Photo Film Co., Ltd., Japan  
 SOURCE: Jpn. Kokai Tokkyo Koho, 47 pp.  
 CODEN: JKXXAF  
 DOCUMENT TYPE: Patent  
 LANGUAGE: Japanese  
 FAMILY ACC. NUM. COUNT: 1  
 PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 2001042532	A2	20010216	JP 1999-211367	19990726
PRIORITY APPLN. INFO.:			JP 1999-211367	19990726

IT 324761-53-7P 324761-58-2P  
 RL: SPN (Synthetic preparation); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)  
 (alicyclic polymer in pos.-working photoresist compn.)  
 RN 324761-53-7 CAPLUS  
 CN 2-Propenoic acid, 2-methyl-, 1-(3-hydroxytricyclo[3.3.1.1<sup>3,7</sup>]dec-1-yl)-1-methylethyl ester, polymer with tetrahydro-2-methyl-5-oxo-3-furanyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

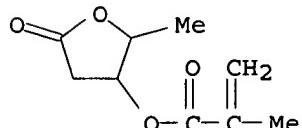
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CRN 324761-49-1  
 CMF C17 H26 O3



CM 2

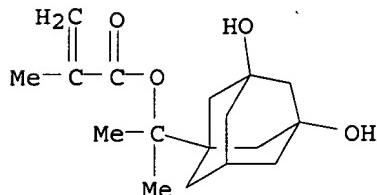
CRN 324761-23-1  
 CMF C9 H12 O4



RN 324761-58-2 CAPLUS  
CN 2-Propenoic acid, 2-methyl-, 1-(3,5-dihydroxytricyclo[3.3.1.13,7]dec-1-yl)-1-methylethyl ester, polymer with tetrahydro-4,4-dimethyl-2-oxo-3-furanyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

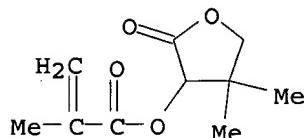
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CRN 324761-57-1  
CMF C17 H26 O4



CM 2

CRN 156938-13-5  
CMF C10 H14 O4



L20 ANSWER 8 OF 8 CAPLUS COPYRIGHT 2003 ACS DUPLICATE 8  
ACCESSION NUMBER: 2001:98658 CAPLUS  
DOCUMENT NUMBER: 134:170817  
TITLE: Positive-working photoresist composition for exposure to far ultraviolet light  
INVENTOR(S): Sato, Kenichiro; Kodama, Kunihiko; Aogo, Toshiaki  
PATENT ASSIGNEE(S): Fuji Photo Film Co., Ltd., Japan  
SOURCE: Jpn. Kokai Tokkyo Koho, 47 pp.  
CODEN: JKXXAF  
DOCUMENT TYPE: Patent  
LANGUAGE: Japanese  
FAMILY ACC. NUM. COUNT: 1  
PATENT INFORMATION:

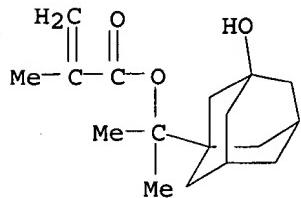
2/9/01

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 2001033969	A2	20010209	JP 1999-203676	19990716
PRIORITY APPLN. INFO.:			JP 1999-203676	19990716

IT 324761-53-7P 324761-58-2P  
RL: IMF (Industrial manufacture); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)  
(pos.-working photoresist compn. contg. polymer with alicyclic group for exposure to far UV light)  
RN 324761-53-7 CAPLUS  
CN 2-Propenoic acid, 2-methyl-, 1-(3-hydroxytricyclo[3.3.1.13,7]dec-1-yl)-1-methylethyl ester, polymer with tetrahydro-2-methyl-5-oxo-3-furanyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

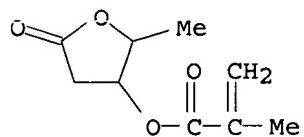
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CRN 324761-49-1  
CMF C17 H26 O3



CM 2

CRN 324761-23-1  
CMF C9 H12 O4

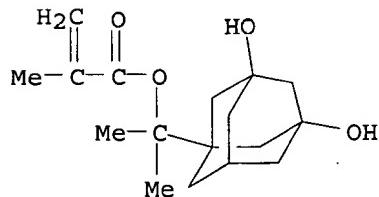


RN 324761-58-2 CAPLUS

CN 2-Propenoic acid, 2-methyl-, 1-(3,5-dihydroxytricyclo[3.3.1.13,7]dec-1-yl)-1-methylethyl ester, polymer with tetrahydro-4,4-dimethyl-2-oxo-3-furanyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

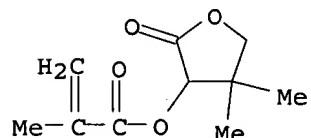
CM 1

CRN 324761-57-1  
CMF C17 H26 O4



CM 2

CRN 156938-13-5  
CMF C10 H14 O4





# Patent Assignment Abstract of Title

**Total Assignments: 2**
**Application #: 09703677 Filing Dt: 11/02/2000 Patent #: 6440636 Issue Dt: 08/27/2002**
**PCT #: NONE**
**Publication #: NONE Pub Dt:**
**Inventors:** Toru Ushirogouchi, Takeshi Okino, Koji Asakawa, Naomi Shida, Yoshinori Funaki, Kiyoharu Tsutsumi, Akira Takaragi, Keizo Inoue

**Title:** POLYMERIC COMPOUND AND RESIN COMPOSITION FOR PHOTORESIST

**Assignment: 1**

<b>Reel/Frame:</b> <u>011434/0499</u>	<b>Received:</b> 01/22/2001	<b>Recorded:</b> 11/02/2000	<b>Mailed:</b> 03/29/2001	<b>Pages:</b> 3
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**Conveyance:** ASSIGNMENT OF ASSIGNORS INTEREST (SEE DOCUMENT FOR DETAILS).

<b>Assignors:</b> <u>USHIROGOUCHI, TORU</u>	<b>Exec Dt:</b> 10/23/2000
<u>OKINO, TAKESHI</u>	<b>Exec Dt:</b> 10/23/2000
<u>ASAKAWA, KOJI</u>	<b>Exec Dt:</b> 10/23/2000
<u>SHIDA, NAOMI</u>	<b>Exec Dt:</b> 10/23/2000

<b>Assignee:</b> <u>KABUSHIKI KAISHA TOSHIBA</u>
72 HORIKAWA-CHO, SAIWAI-KU
KAWASAKI-SHI KANAGAWA-KEN, JAPAN

<b>Correspondent:</b> BIRCH, STEWART, KOLASCH & BIRCH, LLP
RAYMOND C. STEWART
P.O. BOX 747
FALLS CHURCH, VA 22040-0747

**Assignment: 2**

<b>Reel/Frame:</b> <u>011434/0506</u>	<b>Received:</b> 01/22/2001	<b>Recorded:</b> 11/02/2000	<b>Mailed:</b> 03/29/2001	<b>Pages:</b> 3
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**Conveyance:** ASSIGNMENT OF ASSIGNORS INTEREST (SEE DOCUMENT FOR DETAILS).

<b>Assignors:</b> <u>FUNAKI, YOSHINORI</u>	<b>Exec Dt:</b> 10/23/2000
<u>TSUTSUMI, KIYOHARU</u>	<b>Exec Dt:</b> 10/23/2000
<u>TAKARAGI, AKIRA</u>	<b>Exec Dt:</b> 10/23/2000
<u>INOUE, KEIZO</u>	<b>Exec Dt:</b> 10/23/2000

<b>Assignee:</b> <u>DAICEI CHEMICAL INDUSTRIES, LTD.</u>
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<b>Correspondent:</b> BIRCH STEWART KOLASCH ET AL
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Search Results as of: 5/20/2003 6:34:27 P.M.

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 Web interface last modified: Oct. 5, 2002

# Patent Assignment Abstract of Title

Total Assignments: 1

Application #: 09463059

Filing Dt: 01/19/2000

Patent #: NONE

Issue Dt:

PCT #: NONE

Publication #: NONE

Pub Dt:

Inventor: TATSUYA NAKANO

Title: ACID-SENSITIVE COMPOUND AND RESIN COMPOSITION FOR PHOTORESIST

Assignment: 1

Reel/Frame: 010634/0922 Received: 03/29/2000 Recorded: 01/19/2000 Mailed: 06/05/2000 Pages: 3

Conveyance: ASSIGNMENT OF ASSIGNORS INTEREST (SEE DOCUMENT FOR DETAILS).

Assignor: NAKANO, TATSUYA

Exec Dt: 01/08/2000

Assignee: DAICEL CHEMICAL INDUSTRIES, LTD.

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OSAKA 590-8501, JAPAN

Respondent: BIRCH, STEWART, KOLASCH & BIRCH, LLP

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Search Results as of: 5/20/2003 6:28:02 P.M.

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Web interface last modified: Oct. 5, 2002